

WHAT IS CLAIMED IS:

1. An exposure method comprising the steps of:  
illuminating a pattern formed on a mask using  
5 an illumination system that forms an effective light  
source having a first part that includes only s-  
polarized light and a second part that mixes s-  
polarized light and p-polarized light; and  
projecting, through a projection optical  
10 system, light from the mask onto an object to be  
exposed.
2. An exposure method according to claim 1,  
wherein the first part has an annular shape in which  
15 the s-polarized light polarizes in a tangential  
direction of the annular shape.
3. An exposure method according to claim 2,  
wherein the second part has a circular shape that is  
20 located inside the first part.
4. An exposure method according to claim 2,  
wherein the second part has an annular shape that is  
located inside the first part.

5. An exposure method according to claim 1,  
wherein light intensity of the second part is smaller  
than that of the first part.

5       6. An exposure method that uses an illumination  
system that forms a predetermined effective light  
source using light from a light source to illuminate a  
mask, and projects a pattern formed on the mask onto an  
object to be exposed via a projection optical system,  
10 said exposure method comprising the steps of:

            splitting the light into s-polarized light  
and p-polarized light; and

15      forming a first frequency component among  
frequency components of the effective light source by  
inputting the s-polarized light into a surface  
approximately conjugate with a pupil of the projection  
optical system, and forming a second frequency  
component lower than the first frequency component by  
inputting a mixture of the s-polarized light and p-  
20 polarized light into the surface.

7. An exposure method according to claim 6,  
wherein said forming step is conducted at a side closer  
to the light source than an optical integrator provided  
25 between the light source and the mask.

8. An exposure method that exposes a pattern formed on a mask onto an object via a projection optical system using light from a light source, said exposure method comprising the steps of:

5 splitting the light into s-polarized light and p-polarized light; and

inputting the s-polarized light into a predetermined area of a pupil in the projection optical system, and inputting light that mixes the s-polarized 10 light and the p-polarized light inside the predetermined area of the pupil.

9. An exposure method that exposes a pattern formed on a mask onto an object via a projection 15 optical system using light from a light source, said exposure method comprising the steps of:

splitting the light into s-polarized light and p-polarized light; and

introducing the s-polarized light into a 20 first part around a center axis that passes through a center of a pupil, in a periphery around the pupil of the projection optical system, and a mixture of the s-polarized light and the p-polarized light into a second part other than the first part in the periphery around 25 the pupil, the first part being parallel to a periodic direction of the pattern.

10. An exposure method according to claim 9,  
wherein said introducing step introduces the s-  
polarized light into a third part around the center  
axis and an axis orthogonal to the center axis in the  
5 periphery around the pupil of the projection optical  
system, and a mixture of the s-polarized light and the  
p-polarized light into a fourth part other than the  
third part.

10 11. An exposure method according to claim 9,  
wherein the polarization direction is controlled so  
that the desired pattern is resolved by s-polarization  
light and the auxiliary pattern is prevented from  
resolving by the light that mixes the s-polarization  
15 light and the p-polarization light.

12. An exposure method that uses plural types of  
light to project onto an object to be exposed through a  
projection optical system, a mask that arranges a  
20 desired pattern of an auxiliary pattern smaller than  
the desired pattern so that the desired pattern is  
resolved and the auxiliary pattern is prevented from  
resolving, said exposure method comprising the step of  
forming a predetermined effective light source by  
25 controlling a polarization direction.

13. An illumination system comprising a mechanism  
that forms an effective light source by inputting s-  
polarized light into a frequency component for  
resolving a fine pattern, and by inputting light that  
5 mixes the s-polarization light and p-polarization light  
into a frequency component that resolves a pattern  
other than the fine pattern.

14. An illumination system comprising an  
10 effective light source that includes a first part that  
includes only s-polarized light, and a second part that  
mixes the s-polarized light and p-polarized light.

15. An exposure apparatus comprising an exposure  
15 mode that may execute an exposure method that includes  
the steps of illuminating a pattern formed on a mask  
using an illumination system that forms an effective  
light source having a first part that includes only s-  
polarized light and a second part that mixes s-  
20 polarized light and p-polarized light, and projecting  
light from the mask onto an object to be exposed  
through a projection optical system.

16. An exposure apparatus comprising:  
25 an illumination optical system that has an  
effective light source that includes a first part that

includes only s-polarized light, and a second part that mixes the s-polarized light and p-polarized light; and  
a projection optical system that uses the effective light source formed by said illumination  
5 optical system to project a pattern formed on a reticle or mask onto an object to be exposed.

17. A device fabricating method comprising the steps of:  
10 exposing an object using an exposure apparatus; and  
performing a predetermined process for the object that has been exposed,  
wherein the exposure apparatus includes:  
15 an illumination optical system that has an effective light source that includes a first part that includes only s-polarized light, and a second part that mixes the s-polarized light and p-polarized light; and  
a projection optical system that uses the  
20 effective light source formed by said illumination optical system to project a pattern formed on a reticle or mask onto an object to be exposed.